APPENDIX *B*
Instructions for electronic publication-ready papers

All papers will be printed in publication-ready format. Publication-ready copy should be prepared according to the following instructions. Please read these carefully, as publication-ready copy that does not conform to these instructions will be returned for correction.

(1) The paper should be submitted according to Section 3 of Notes for Authors. You do not need to prepare the publication-ready copy until your paper has been **accepted** by the Co-editor.

(2) The style of a publication-ready paper in the *Journal of Synchrotron Radiation* is shown on the following pages. The detailed typographic specifications are as follows:

Layout details

Page size (text area):	183 × 238 mm
Column width:	88 mm
Space between columns:	7 mm

Fonts and spacing

Title:	**12 pt bold Helvetica**
Authors:	**10 pt bold Helvetica**
Affiliations:	*9 pt oblique Helvetica*
Abstract:	9 pt Times Roman
Keywords:	**8 pt bold Helvetica**
Headings	
Level 1:	**8 pt bold Helvetica, aligned left**
Level 2:	**8 pt bold Helvetica, aligned left**
Level 3:	**8 pt bold Helvetica, at start of paragraph**
Text:	9 pt Times Roman
References:	8 pt Times Roman
Figure captions:	8 pt Times Roman
Table captions:	8 pt Times Roman
Table text:	7 pt Times Roman
Footnotes:	8 pt Times Roman

If you do not have Helvetica fonts available, please use Univers or another sans-serif font.

(3) Electronic templates (LaTeX and WORD) are available by ftp from the address ftp.iucr.org in the directory 'templates/jsr'. The above styles are already set up in these templates.

(4) Once your paper has been accepted, the Co-editor will ask you to provide (*a*) the completed publication-ready copy, (*b*) an electronic version of the paper in LaTeX or WORD, (*c*) originals of all figures and (*d*) electronic versions of all figures in PostScript, Encapsulated PostScript or TIFF format. Please send the material to the Co-editor in a rigid card envelope to ensure it is not damaged in the post.

(5) When the publication-ready copy has been approved by the Co-editor, it will be forwarded to the Editorial Office in Chester for publication. If additional material is required by the Editorial Office, it should be submitted following the procedures given in Section 3.11 of Notes for Authors.

Design and performance of a multilayered mirror monochromator in the low-energy region of the VUV

Harutaka Mekaru,[a] Tsuneo Urisu,[b]* Yoshiyuki Tsusaka,[c] Shin Masui,[d] Eijiro Toyota[d] and Hisataka Takenaka[e]

[a]The Graduate University for Advanced Studies, Institute for Molecular Science, Myodaiji, Okazaki 444, Japan, [b]Institute for Molecular Science, Myodaiji, Okazaki 444, Japan, [c]Department of Material Science, Himeji Institute of Technology, Kamigori, Akou-gun 678-12, Japan, [d]Sumitomo Heavy Industries Ltd, Yato, Tanashi, Tokyo 188, Japan, and [e]NTT Advanced Technology Corporation, Midori, Musashino, Tokyo 180, Japan. E-mail: urisu@ims.ac.jp

For the energy region from tens to hundreds of electron volts, the multilayered mirror (MLM) monochromator has never been realized due to the difficulty of reducing the background noise of the total reflection component, in spite of its useful[illegible] synchrotron radiation experiments. In this work, a d[illegible] type MLM monochromator equipped wi[illegible] been designed on the basis of t[illegible] driving system and of M[illegible] has been evalua[illegible] shown th[illegible] with an [illegible] practical [illegible] ow background[illegible]

Sample electronic publication-ready paper (not to scale)

Keywords: m[illegible]ayered mirror monochromators.

1. Introduction

Studies of synchrotron-radiation-stimulated processes such as etching and chemical vapour deposition (CVD) began about 12 years ago (Urisu & Kyuragi, 1987) and are still attracting much interest from many researchers. The vacuum ultraviolet (VUV) photons in synchrotron radiation can excite almost all the electronic states of molecules, so a large variety of chemical reaction channels different from that in the usual thermal-CVD are expected to be opened by synchrotron radiation irradiation. In particular, core electrons, which cannot be excited using lasers, are efficiently excited by the VUV photons in synchrotron radiation. The excitation-energy dependence of a photochemical reaction is important basic data. However, it has not been sufficiently investigated in the VUV region, because of the difficulty in obtaining energy-tunable monochromated light with sufficient photon flux (>10^{13} photons s^{-1}) in the VUV region.

A multilayered mirror (MLM) monochromator is already in use in the high-energy region of the VUV (Barbee *et al.*, 1987). Concerning the low-energy regions, one of the present authors previously tried to use an MLM as a dispersion element in synchrotron-radiation-stimulated experiments. However, this was unsuccessful due to the difficulty in removing the background noise, consisting of total reflection components appearing at less than a few tens of eV. Therefore, in this work, we have designed a double-crystal-type MLM (Golovchenko *et al.*, 1981; Murata *et al.*, 1992) monochromator combined with an appropriate thin-film filter. The design is based on the trial fabrication of MLMs and the driving system for them. We have found that the low-energy background noise is sufficiently removed by using the MLMs at low incident angles combined with a carbon or molybdenum filter.

2. Design of the monochromator and mirrors

2.1. Monochromator

We adopted the monochromator driving system proposed by Golovchenko *et al.* (1981). The centres (*A* and *B*, respectively) of the first and the second MLMs are set on the *XY* and *YZ* lines which form a rigid right angle *XYZ*, with the first MLM parallel and the second perpendicular to the *XY* [illegible] lines, respectively. A pulsed motor drive sli[illegible] of the *XYZ* linearly, keeping the ro[illegible]ond mirror fixed. The first m[illegible]ond mirror so that it [illegible] the apex Y[illegible] so that [illegible] in an [illegible] using the [illegible]ement is also effec[illegible] higher-order photons. The [illegible]creases as the incident angle to the [illegible] mechanical linkage and driving system have [illegible]ed so that the beam incident angle can be adjusted [illegible] incident angles as small as possible. The present prototype driving system has successfully covered an incident beam angular range (θ) of 10–80°.

2.2. MLMs

The important photon energy region for the experimental investigation of synchrotron radiation processes, especially of the core-electron excitation processes, is from a few tens to hundreds of electron volts. In the present work our attention was focused on the region between 60 and 120 eV, a region for which fairly high reflectivity is obtained by using Mo/Si (for 60−90 eV) and

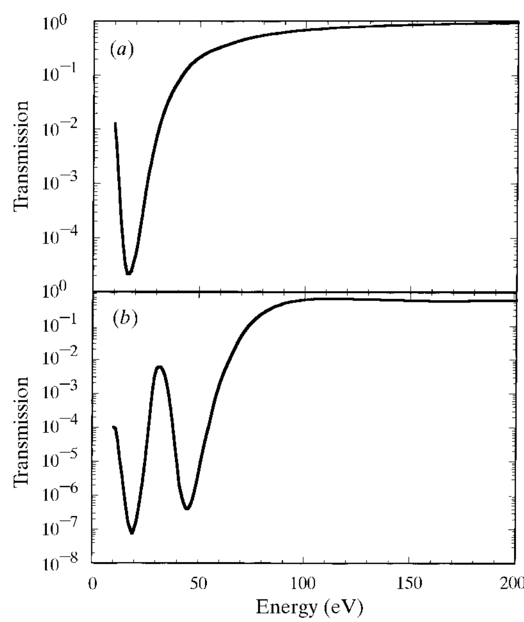

Figure 1
The calculated transmission for (*a*) a 100 nm-thick carbon filter and (*b*) a 100 nm-thick molybdenum filter.

238 mm

88 mm

183 mm

Table 1
Specifications of optical components.

Component	Specifications	
Mo/Si MLM	Substrate	Si wafer (40 × 40 mm)
	Number of layers	20
	Period, d	12.5 nm (12.4 nm)†
	Thickness ratio, Mo/Si	3/7 (3.25/6.75)†
	Interface roughness, σ	(0.4 nm)†
Mo/C MLM	Substrate	Si wafer (40 × 40 mm)
	Number of layers	50
	Period, d	7.5 nm (7.9 nm)†
	Thickness ratio, Mo/C	1/1 (5.5/4.5)†
	Interface roughness, σ	(0.4 nm)†

† Values determined by fitting to the observed Cu $K\alpha$ line diffraction curves.

Mo/C (for 85–120 eV) MLMs. This energy region includes the core-electron binding energies of Al (2*s*: 119 eV; 2*p*: 74 eV) and Si (2*p*: 103 eV), which are important materials in semiconductor processes. To reduce the background noise in the low-energy region due to the total reflection, it is necessary to use the MLM at low incident angles. The Mo/Si and Mo/C MLMs were therefore designed so that they could cover the Al 2*s* and 2*p* and Si 2… binding energies in the incident angle range of 10–50°… more, the detailed structural parameters hav… that the reflectivity is high and the re… trical. Both Mo/Si and Mo/C … meters listed in Table … using the Cu … Corpora… between … roughness … ett & Porteus, 19… diffraction data, are listed in…

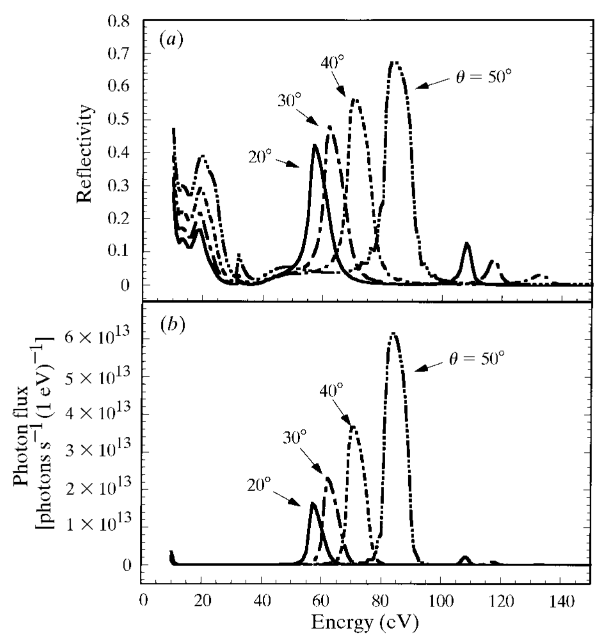

Figure 2
(*a*) Calculated reflectivity for the Mo/Si MLM and (*b*) output photon flux of the monochromator using Mo/Si MLMs plus C filter for a 100 mA ring current and a 16.56 × 12.79 mrad^2 acceptance angle of the pre-mirror, assuming that the monochromator is set up in the beamline BL-4A1 of the UVSOR.

2.3. Thin-film filters

The transmission characteristics of the thin-film filter have been calculated for several materials and it has been found that carbon and molybdenum are useful for reducing the background noise at energies below 70 eV. The transmission spectra calculated for 100 nm-thick carbon and molybdenum film filters are shown in Figs. 1(*a*) and 1(*b*), respectively.

3. Performance of the monochromator

The performance of the MLM monochromator, designed as described above, was evaluated by calculating what the basic characteristics, such as output photon flux, resolution, monochromaticity and tuning range, would be if the monochromator were set up as part of the beamline (BL4A… synchrotron radiation storage ring at the UVSO… ne, the beam emitted from the bendin… is reflected by an elliptical … ngle of 4°. The hori… 0 cm and … m from … 6.1 m … about 0.5 × … as calculated for a … the recurrent equation (Spiller, … and Mo/C MLMs were first calculated by …rror parameters listed in Table 1, as shown in Fig. 2(*a*) …he Mo/Si case. It is known that extremely large total-reflection components appear at less than 40 eV in the case of Mo/Si.

The output beam photon fluxes calculated for various incident angles are shown in Fig. 2(*b*) for the case of Mo/Si MLM plus C filter. It is clearly shown that the filter drastically reduces the low-energy background noise. It is less than 1% (3%) of the main flux, where the value in parentheses is for the case of Mo/C MLM plus Mo filter. The higher-order photons background noise is less than 4% (0.1%). The calculated photon flux is 1×10^{14} to 5×10^{14} photons s^{-1} (3×10^{13} to 4×10^{13} photons s^{-1}) and the resolution is 5–9 eV (2–4 eV) FWHM. The calculated results are similar to those obtained with a typical undulator. Given that the MLM monochromator can select the photon energy continuously and that the mixing of higher-order photons is small, it is suggested that the present monochromator will be better than an undulator for use in synchrotron radiation experiments. We conclude from this work that the background noise due to the total reflection, which prevented the MLM monochromator from being used in the VUV low-energy region, can be sufficiently reduced by using double-crystal-type MLMs at low incident angles combined with a carbon or molybdenum thin-film filter.

This research was supported in part by a Collaboration Program of the Graduate University for Advanced Studies.

References

Barbee, T. W. Jr, Pianetta, P., Redaelli, R., Tatchyn, R. & Barbee, T. W. III (1987). *Appl. Phys. Lett.* **50**(25), 1841–1843.
Bennett, H. E. & Porteus, J. O. (1961). *J. Opt. Sci. Am.* **51**(2), 123–129.
Golovchenko, J. A., Levesque, R. A. & Cowan, P. L. (1981). *Rev. Sci. Instrum.* **52**(4), 509–516.
Murata, T., Matsukawa, T., Naoe, S., Horigome, T., Matsudo, O. & Watanabe, M. (1992). *Rev. Sci. Instrum.* **63**(1), 1309–1312.
Spiller, J. (1981). *AIP Conf. Proc.* **75**, 124–130.
Urisu, T. & Kyuragi, H. (1987). *J. Vac. Sci. Technol.* B**5**, 1436–1440.

238 mm

88 mm

183 mm